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Application Number TO BE ASSIGNED (Div1)

Filing Date March 8, 2002

First Named Inventor Bruce W. Smith

Group Art Unit 2851

Examiner Name Hung NGUYEN

Attorney Docket Number 81468, 284420

				U.S. PATENT DOC	UMENTS	
xaminer nitials*	Cite No.1	U.S. Paten Number	t Document Kind Code² (if known)	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
M	1	5,627,625		Tohru Ogawa	05/06/97	
	2	5,638,211		Naomasa Shiraishi	06/10/97	
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Examiner Initials	Cite No.1		Foreign Patent Do	cument	Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	\top
		Office ³	Number ⁴	Kind Code ⁵ (if known)				1.e
HW	9	EP	0 503 472 A3	EP	Minori Noguchi	09/16/92		
	10	EP	0 500 393 B1	EP	Akiyoshi Suzuki, et al.	08/26/92		
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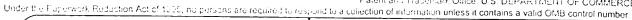
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Substitu	ute for form 1449B/P1	го		Complete if Known					
	ODMATIO		1001 001155	Application Number	TO BE ASSIGNED (DIV1) 9	,			
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STA	TEMENT	BY	APPLICANT	First Named Inventor	Bruce W. Smith	7			
			,	Group Art Unit	2851	•			
	(use as many	sheet	s as necessary)	Examiner Name	Hung NGUYEN	>			
heet	2	of	2	Attorney Docket Number		7			

		OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS	<u>.,</u>
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
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